

# TCAD simulation VIII

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# Overview

- **Simulation example of 2D PN junction using SPROCESS and SDEVICE**
- **Charge generation and collection**

# TCAD Synopsys Simulation

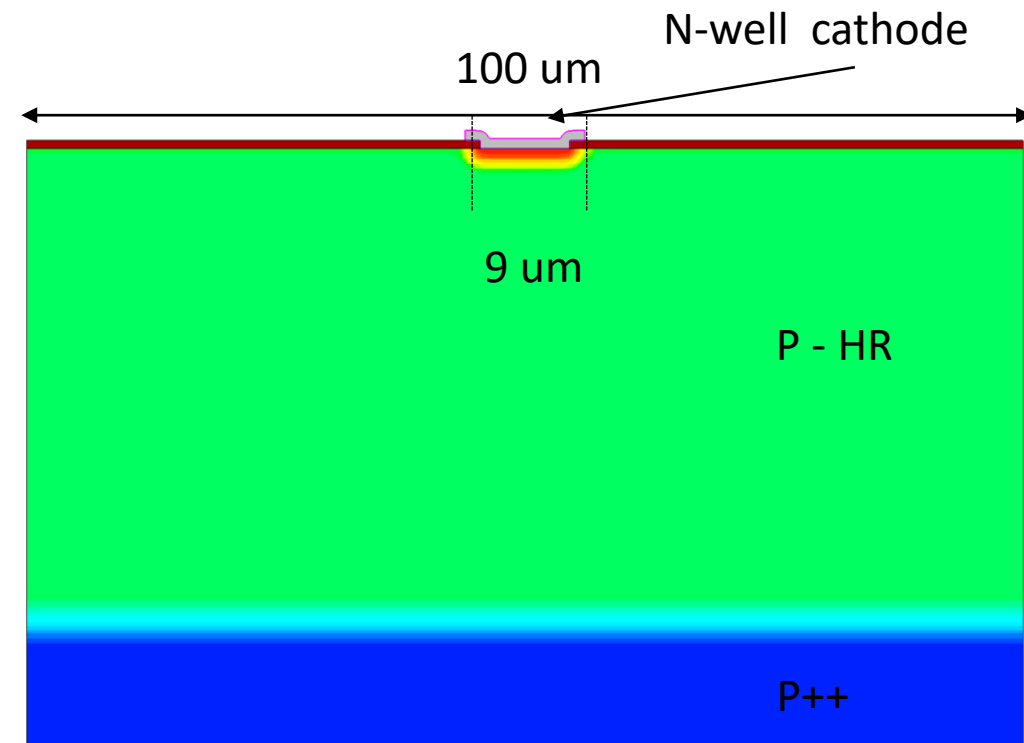
- SDEVICE simulation of 2D pn junction
  - **Charge generation**
- **Within SDEVICE, charge injection by particles can be modelled using the models for carrier generation by gamma radiation, alpha particles and heavy ions (optical generation is also available)**
- **HeavyIon generation:**

Glet: linear energy transfer(LET) generation density

R(w,t): spatial distribution (exponential/Gaussian)

T(t): temporal profile

			
deviceIV_FW	deviceCV_RE	TwoDsprocessHIT	sdeviceCCE
[n7] --	[n10] --	[n31] --	y
		[n30] -5	[n16] --
			[n13] 100



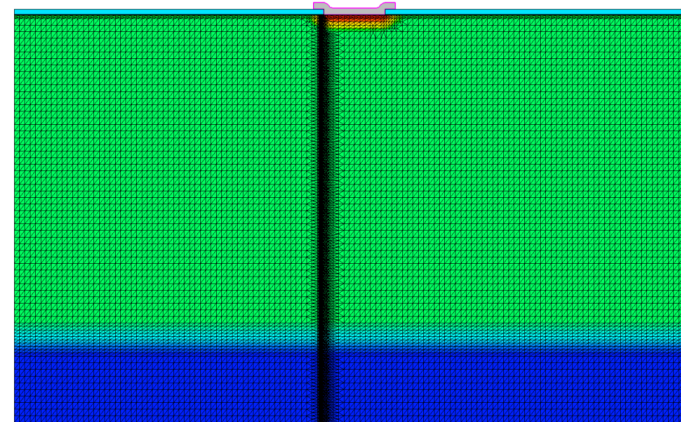
## TCAD Synopsys Simulation

- Additional SPROCESS to increase the mesh resolution in the region of the hit: vertical hit at coordinate (0,Y)
- SDEVICE command file: physics section

```
### if {$HIT} {  
## MIP  
### From G4 MIP sims, the meshing in the track region needs to be as small as  
nm's...
```

```
refinebox Silicon name= HIT min= {0 @<@y@-0.1>@} max=  
{@<@Epi_thick@+@Sub_thick@>@ @<@y@+0.1>@} xrefine= {.05 .05 .05}  
yrefine= { .05 .05 .05}
```

```
### }
```



# TCAD Synopsys Simulation

- SDEVICE command file: physics section
  - **The ionisation is obtained by a Minimum Ionising Particle (MIP)**
  - **Details of the ionisation are included in a file (MIP\_EXC) which has the LET and spatial parameters required for MIP emulation**

```
Physics {  
  
#####if "@Ionization@"=="MIP"  
  
#include "MIP_EXC"  
  
...  
  
#define WT_hi 0.1  
  
        Heavylon (  
Time = HitTime  
Location = (0, 0) ### Hits at the top surface, right in the middle of the device  
Direction = (1.0,0.0)      ### Perpendicular hit  
  
###LET_f = [1.28e-5 1.28e-5 1.28e-5] ### 80 e/h per micron is 1.28E-5 for THICK sensor  
LET_f = [1.056e-5 1.056e-5 1.056e-5] ### 66 e/h per micron as MPV for 50 um thick  
active region  
### LET_f = [1.15e-5 1.15e-5 1.15e-5] ### 72 e/h per micron as MPV for 300 um thick  
active region  
  
Wt_hi = [WT_hi WT_hi WT_hi] ###      ro = 0.1/0.2 micron  
Length = [ 0.0 20 60 ] ### LET @ different depths, irrelevant for a MIP  
PicoCoulomb  
Gaussian  
  
        )
```

## TCAD Synopsys Simulation

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- MIP transient
  - **Effects due to different bias**
  - **Charge collection vs. hit location**
  - **Charge collection vs. meshing resolution**
  - **Charge collection vs. doping**

**Thank you**

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- Simulation example : 2D pn using SPROCESS
- MIP Charge generation and collection